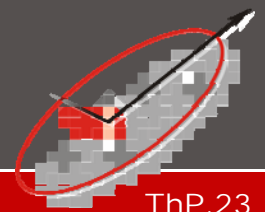


# Angle-resolved Generalized Ellipsometry: Form-birefringent chiral and non-chiral silicon sculptured thin films



UNIVERSITY OF NEBRASKA-LINCOLN



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D. Schmidt\*, E. Schubert, and M. Schubert

Department of Electrical Engineering and Nebraska Center for Materials and Nanoscience, University of Nebraska-Lincoln, U.S.A.

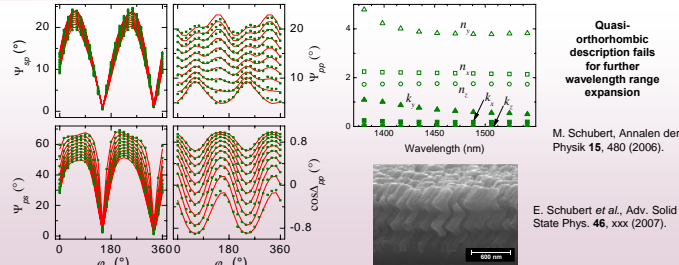
\*schmidt@bigred.unl.edu

ellipsometry.unl.edu

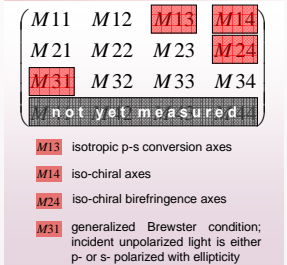
## Our message

- Generalized Ellipsometry permits analysis of intrinsic axes and response functions in dielectric anisotropic materials, regardless of symmetry (tetragonal, orthorhombic, triclinic).
- New material classes emerge with nano structure thin film fabrication.
- 3D angle-resolved spectroscopic Mueller matrix studies identify new optical signatures beyond dielectric anisotropy in nano structured chiral silicon thin films.
- Symmetry violation, which cannot be explained by dielectric birefringence, hints to necessary introduction of chiral tensor description (optical activity = bianisotropy).

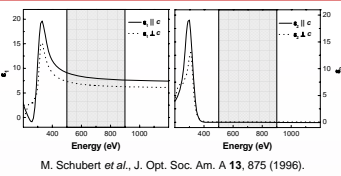
## Quasi-orthorhombic description for silicon chevron



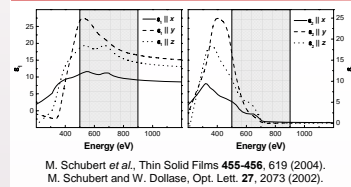
## 3D Mueller matrix image



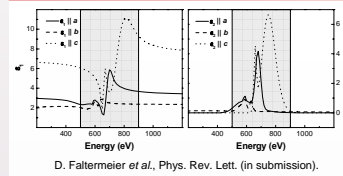
## Rutile (111) surface (tetragonal; α = β = γ = 90°)



## Stibnite (313) surface (orthorhombic; α = β = γ = 90°)



## Pentacene (011) surface (triclinic; α ≠ β ≠ γ ≠ 90°)



## Silicon nano spirals (pseudo-triclinic + chiral)

